

# Atomic-scale Structure of the Ba/Si(001) – (2 × 1) Surface: X-ray Standing Wave Analysis

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## Introduction

Submonolayer (sub-ML) surface phases of alkaline earth metals on Si(001) have been of interest recently due to their role as a precursor to the growth of high-quality perovskite films, such as SrTiO<sub>3</sub> and BaTiO<sub>3</sub>, on Si. A (2 × 1) Ba/Si(001) phase has been reported for Ba coverages ranging from 1/4 to 3/4 ML. There have been conflicting reports over the saturation coverage and atomic-scale structure of this phase [1-4]. In the present work, we use x-ray standing wave (XSW) measurements of a sub-ML (2 × 1) Ba/Si(001) surface to determine the position of Ba atoms relative to the underlying bulk Si lattice.

## Methods and Materials

Experiments were conducted at BESSRC undulator beamline station 12-ID-D at the APS. Molecular beam epitaxy sample preparation, Auger electron spectroscopy (AES), low-energy electron diffraction (LEED), and XSW measurements were performed in an ultrahigh vacuum (UHV) system with a base pressure of  $\sim 1.5 \times 10^{-10}$  torr.

Single-crystal Si(001) samples were treated with a modified Shiraki etch and mounted in a strain-free manner onto molybdenum sample holders prior to introduction into the UHV system. After degassing for  $\sim 12$  hours at 400-600°C, the samples were annealed for 15 minutes at 850-900°C to remove the chemically grown SiO<sub>2</sub> film and produce a sharp, two-domain (2 × 1) LEED pattern, indicating a dimerized Si(001) surface. AES showed C and O contamination levels to be less than 0.02 ML (1 ML =  $6.78 \times 10^{14}$  atoms/cm<sup>2</sup>).

An effusion cell was used to deposit  $\sim 1.3$  ML Ba at a rate of 0.02 ML/min onto the room-temperature Si(001) substrates. Subsequent annealing for 5 minutes at 850°C caused the Ba coverage to decrease to  $0.31 \pm 0.03$  ML and resulted in a sharp (2 × 1) LEED pattern. The Ba coverage was determined in UHV by comparing the intensity of the Ba L $\alpha$  fluorescence from the samples to that of a Ba-implanted Si(001) standard calibrated by Rutherford backscattering spectroscopy (RBS). *Ex situ* RBS was also used to measure the Ba coverage after completion of the XSW experiment. The sample temperature was monitored

by using an optical pyrometer and a thermocouple mounted on the sample stage.

Using an incident photon energy of 8.0 keV, UHV XSW measurements of the (2 × 1) Ba/Si(001) surface were performed by scanning the sample in angles through the silicone (004) and (022) Bragg conditions. The incident beam from the undulator was filtered by a high-heat-load Si(111) monochromator followed by a postmonochromator consisting of a pair of detuned, nondispersive, Si channel-cut crystals. The d-spacing of the postmonochromator matched that of the sample. During each scan, the diffracted beam intensity was monitored with a photodiode, and the x-ray fluorescence spectra were collected by a Si(Li) solid-state detector. The Ba coherent fractions  $f_H$  and coherent positions  $P_H$  were determined by fitting the reflectivity and normalized Ba L $\alpha$  fluorescence yield data to dynamical diffraction theory, as described in Refs. 5 and 6.

## Results

Experimental data and theoretical fits for the silicone (004) and (022) XSW measurements are shown in Fig. 1. The measured  $P_{004} = 0.99$  corresponds to ordered Ba adatoms located at a height just 0.01 Å below a bulk-extrapolated Si(004) atomic plane (note that this height difference is on the same order as the experimental error). The measured  $P_{022} = 0.55$  is in general agreement with the relationship  $P_{022} = P_{004}/2$ , a geometrical symmetry requirement for the occupation of cave or bridge sites on the Si(001) surface.

## Discussion

While several atomic-scale models of the (2 × 1) Ba/Si(001) surface have been proposed [1, 3], only that suggested in Ref. 4 and depicted in Fig. 2 is consistent with our results. This model contains Ba atoms occupying cave sites on a dimerized Si(001) surface and saturates the surface at a coverage of 1/2 ML. Our observation of the (2 × 1) phase at a Ba coverage of just 0.31 ML and the rather modest  $f_H$  values, indicating that  $\sim 1/2$  of the Ba coverage is disordered could be explained by a (2 × 1) phase (with a *local* coverage of 1/2 ML) covering only a fraction of the surface. These findings, however, could

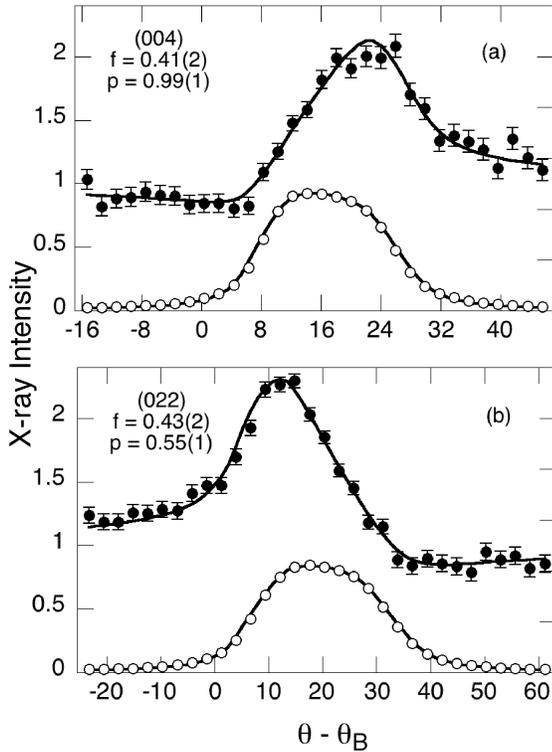


FIG. 1. Reflectivity (open circles) and normalized Ba  $L\alpha$  fluorescence yield (solid circles) experimental data, along with corresponding theoretical fits for the (a) Si(004) and (b) Si(022) XSW measurements.

also be due to the  $(2 \times 1)$  phase exhibiting a saturation coverage less than that shown in Fig. 2, and they illustrate the importance of distinguishing between the ordered and disordered fraction of adatoms when mapping out a surface-phase diagram.

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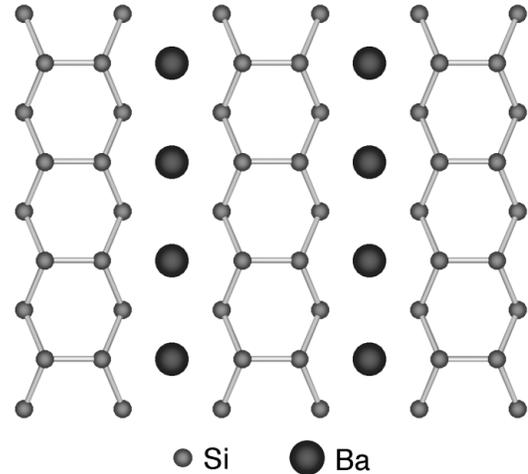


FIG. 2.  $1/2$  ML  $(2 \times 1)$  Ba/Si(001) surface model initially proposed in Ref. 4.

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